Attorney Docket No. 071469-0305918 **PATENT**

Client Reference: RAJ-014

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Noriaki FUKIAGE, Katherina BABICH In re application of:

Application No.: Confirmation

No:

Filed: November 6, 2003

Group No.: Examiner

For:

METHOD OF IMPROVING POST-DEVELOP PHOTORESIST PROFILE ON A

DEPOSITED DIELECTRIC FILM

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

APPLICATION DATA SHEET 37 C.F.R. § 1.76

BIBLIOGRAPHIC DATA

1. Applicant information

First applicant: Noriaki FUKIAGE

Citizenship: JAPAN Residence: Hartsdale, NY

Second applicant: Katherina BABICH

Citizenship: USA

Residence: Chappaqua, NY

2. Correspondence information

Correspondence for this application should be addressed as follows:

Customer No.: 00909

3. Application information

Title of Invention: METHOD OF IMPROVING POST-DEVELOP PHOTORESIST PROFILE ON A DEPOSITED DIELECTRIC FILM

Docket number assigned to this application: 071469-0305918

Suggested Classification: Class:

Subclass:

Technology Center to which subject matter is assigned:

Total number of drawing sheets: 4

Type of application:

Utility

Application is to be published. Suggested drawing figure for publication:

Secrecy order under § 5.2:

This application does not disclose subject matter of an application which is under a secrecy order pursuant to § 5.2.

4. Representative information

The following have a power of attorney or authorization of agent in this application:

Customer No.: 00909

5. Assignee information

The assignee(s) of this application is/are:

Tokyo Electron Limited 3-6, Akasaka 5-chome, Minato-ku Tokyo, 107 JAPAN Extent of interest of assignee in application: 50%

International Business Machines Corporation

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Extent of interest of assignee in application: 50%

Date: November 6, 2003

Reg. No.: 28872

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